



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmation No. 9635**  
Satoshi MAEMORI et al. : Docket No. 2001\_1300A  
Serial No. 09/955,111 : Group Art Unit 1752  
Filed September 19, 2001 : Examiner Sin Lee

POSITIVE-WORKING PHOTORESIST  
COMPOSITION AND PHOTSENSITIVE  
MATERIAL USING SAME

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**RESPONSE TO FINAL REJECTION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Final Rejection dated September 5, 2003, the period for response having been extended by the filing of the accompanying RCE and Petition for Three Month Extension of Time, please amend the present application as follows:

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TC 1700